

Supplementary Material

Continuous-Flow Bioseparation Using Microfabricated Anisotropic Nanofluidic Sieving Structures

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This supplementary material includes

Supplementary Figure S1 with caption

Figure S1

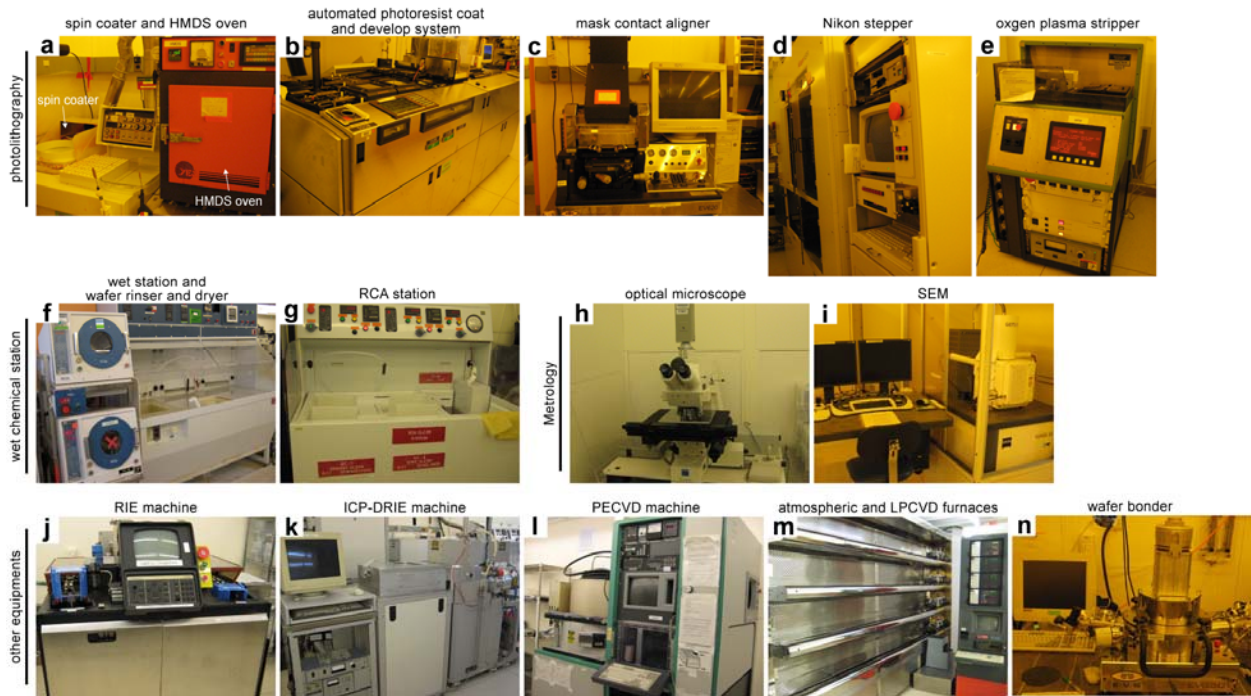


Figure S1 | Cleanroom equipments used for fabrication of the ANA structures. They include the photolithography equipments (spin coater and HMDS oven (a), automated photoresist coat and develop system (b), mask contact aligner (c), Nikon stepper (d), and oxygen plasma stripper (e)), wet chemical stations (wet chemical station and wafer rinser and dryer (f) and RCA station (g)), metrology tools (optical microscope (h) and SEM (i)), and other equipments for dry etching (RIE machine (j), ICP-DRIE machine (k)), deposition (PECVD machine (l), atmospheric and LPCVD furnaces (m)), and bonding (wafer bonder (n)).